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12cm RF w/ RFN Source Checkout

These data are representative of a 12 cm RF/RFN extension mount source with 8 cm pattern grids. Actual run data will vary with specific system conditions.
Data obtained on Techne prototype system. Gas flows are 4 sccm Argon RFNs, 16 sccm Argon 16 cm, 10 sccm Oxygen 12 cm, 15 sccm Oxygen Titanium target.
These data are for general information purposes only.

Gas Flow	**Gas Flow**	**Gas Type**	**Chamber**	**Beam**		**Accel**		**RF**		**Neutralizer**		**Comments**
Source	RFN		Pressure	Current	Voltage	Current	Voltage	FWD	REF	Emission	RF FWD	other info
[sccm]	[sccm]		[x10-4 Torr]	[mA]	[V]	[mA]	[V]	[W]	[W]	[mA]	[W]	
			base pressure is 2.9x10-7 Torr									
Source Warmup												
10.0	4.0	Ox/Ar	5.7	9	50	0	150	251	0	500	50	all process gasses are ON
Source Check-out / Beam Envelope Check												
10.0	4.0	Ox/Ar	5.7	100	100	3	600	224	0	150	40	
10.0	4.0	Ox/Ar	5.7	200	100	6	900	369	0	300	50	
10.0	4.0	Ox/Ar	5.7	100	250	2	500	221	0	150	40	
10.0	4.0	Ox/Ar	5.7	250	250	7	900	427	0	375	50	
10.0	4.0	Ox/Ar	5.7	300	250	9	1000	486	0	450	50	
10.0	4.0	Ox/Ar	5.7	100	500	2	150	227	0	150	40	
10.0	4.0	Ox/Ar	5.7	250	500	6	600	420	6	375	50	
10.0	4.0	Ox/Ar	5.7	300	500	7	800	475	0	450	50	
10.0	4.0	Ox/Ar	5.7	100	750	1	150	220	0	150	40	
10.0	4.0	Ox/Ar	5.7	300	750	6	500	492	0	450	50	
10.0	4.0	Ox/Ar	5.7	100	1000	1	150	208	0	150	40	
10.0	4.0	Ox/Ar	5.7	300	1000	5	400	472	0	450	50	
10.0	4.0	Ox/Ar	5.7	100	1250	1	150	203	0	150	40	
10.0	4.0	Ox/Ar	5.7	200	1250	2	150	337	0	300	50	
10.0	4.0	Ox/Ar	5.7	300	1250	4	150	472	0	450	50	
10.0	4.0	Ox/Ar	5.7	100	1500	1	150	198	0	150	40	
10.0	4.0	Ox/Ar	5.7	300	1500	4	150	465	0	450	50	
Total Time on source:				min.								